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Triode Plasma Chamber

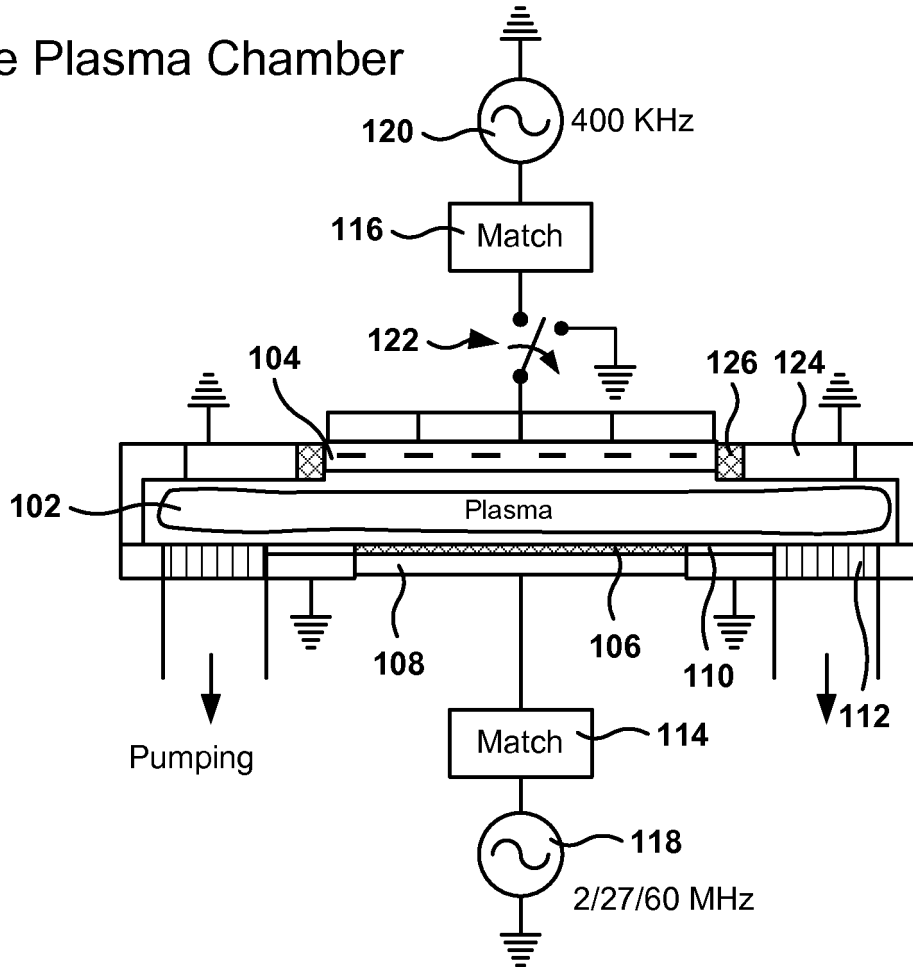


Fig. 1

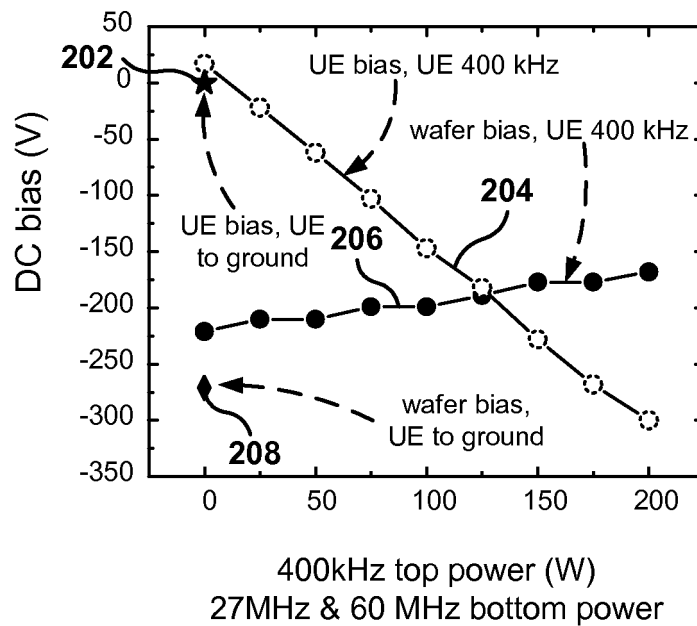


Fig. 2

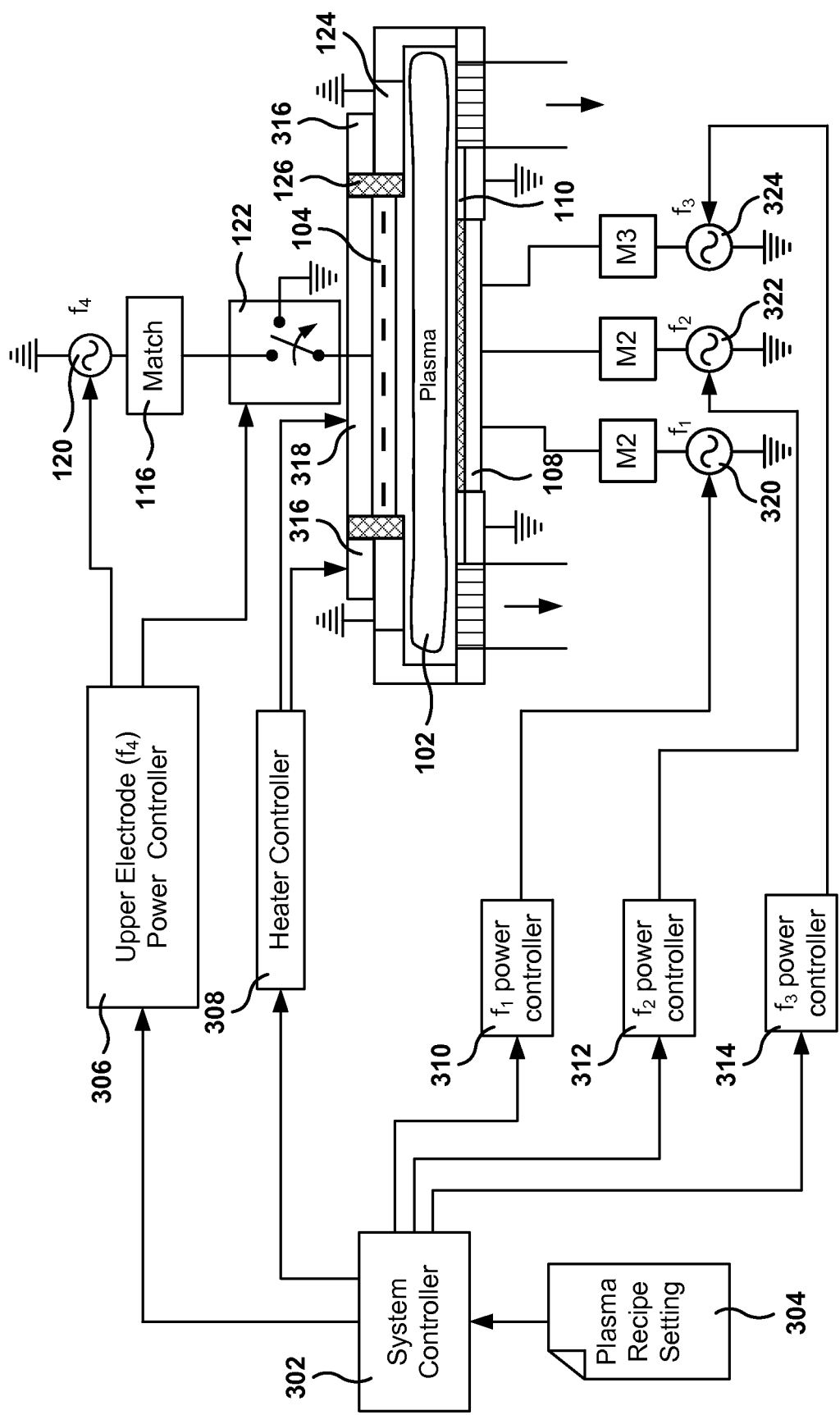


Fig. 3

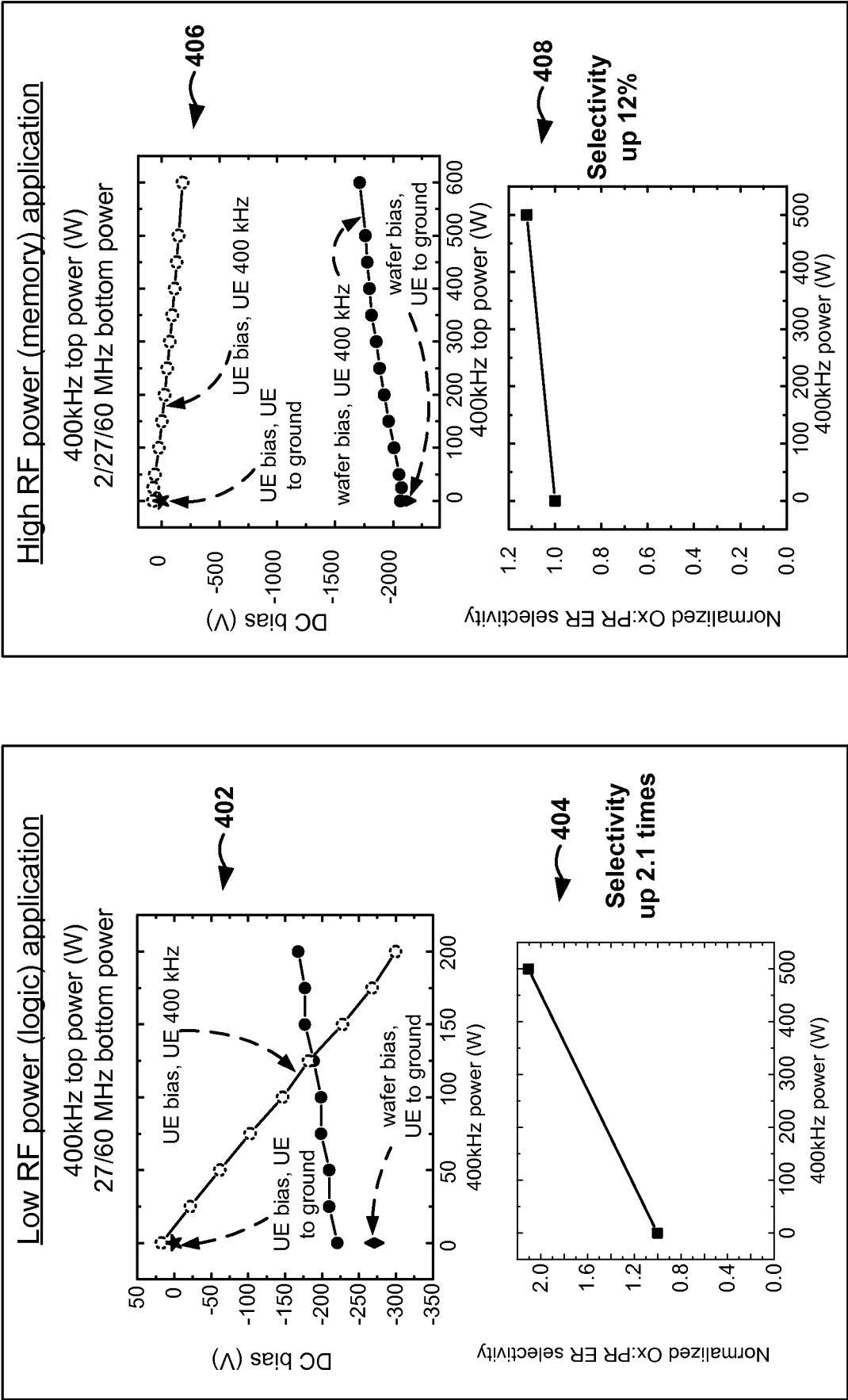


Fig. 4A

Fig. 4B

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Oxide etch rate radial uniformity control with top power

Power on upper electrode improves radial etch rate uniformity

400kHz top power 0W, 500W, 700W

60MHz bottom power, 400W

Radial Uniformity 3σ : 32% to 3%

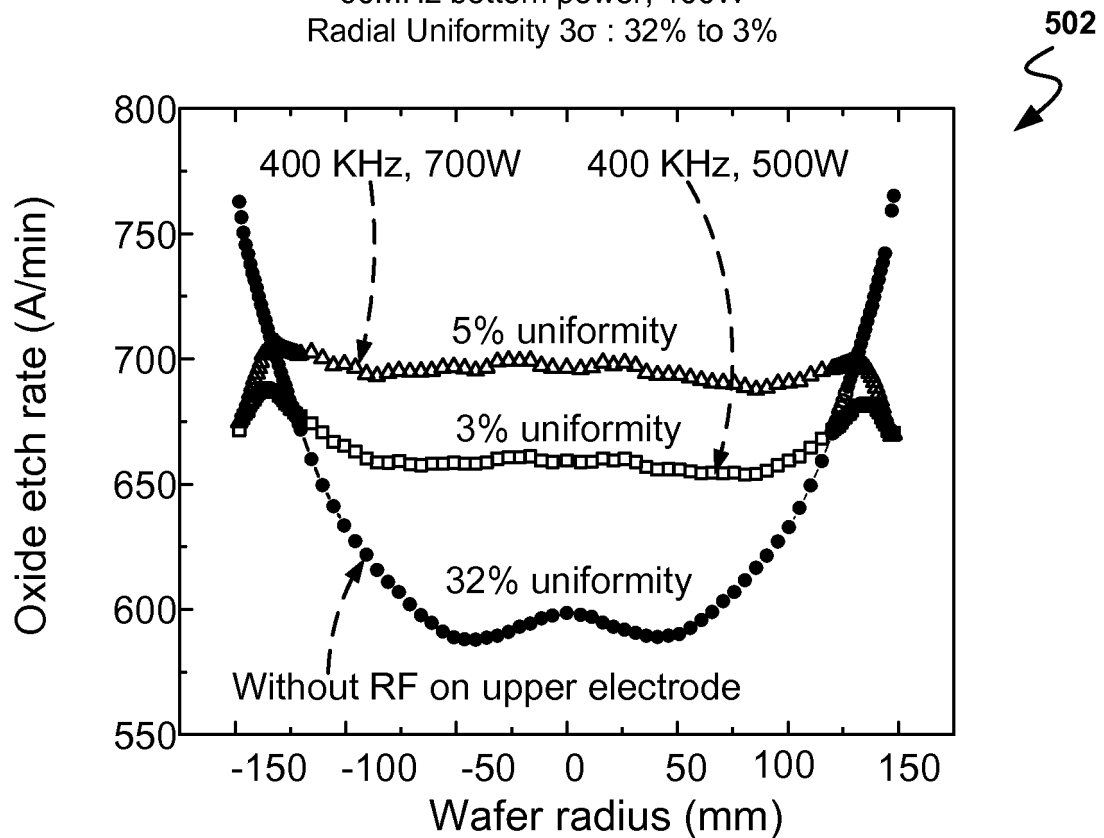


Fig. 5A

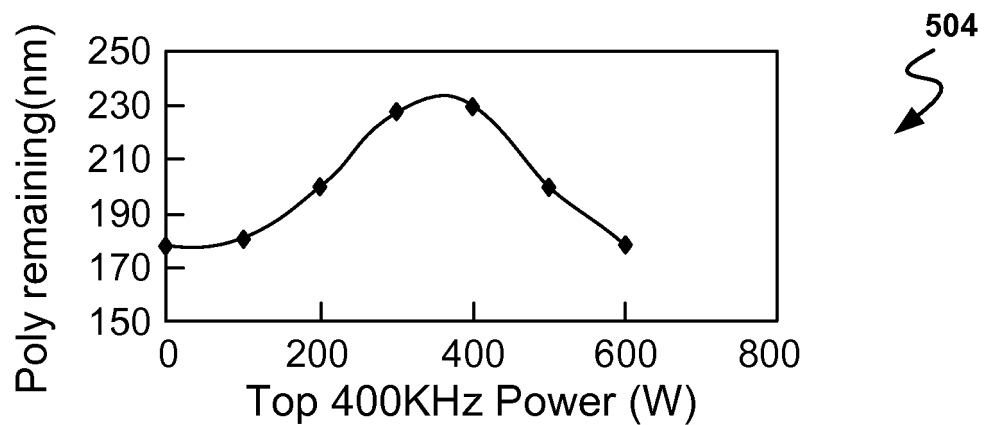


Fig. 5B

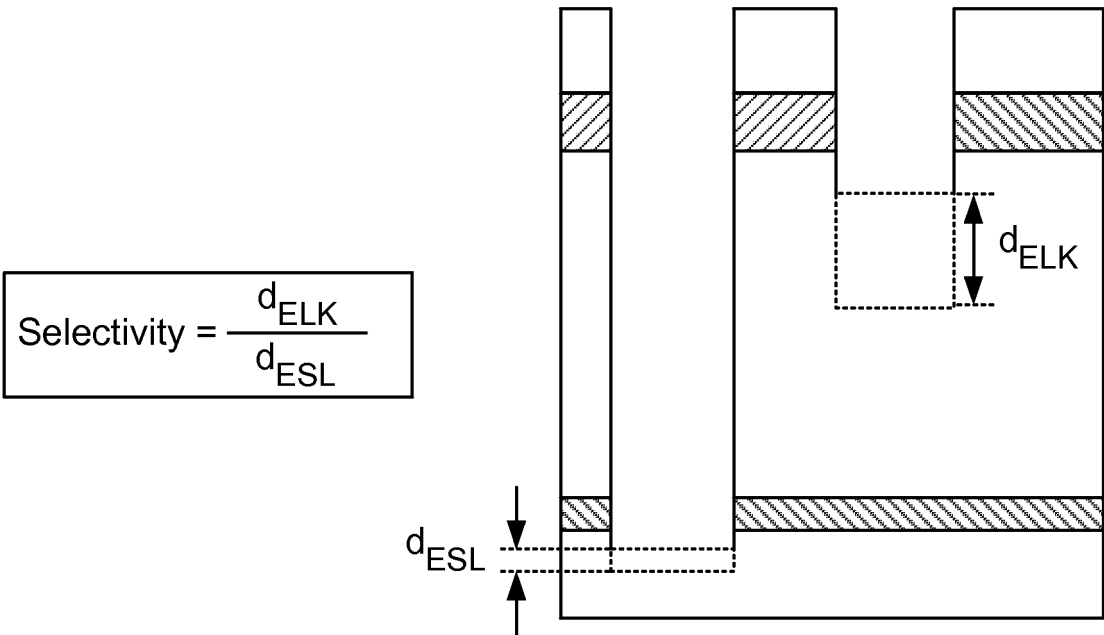


Fig. 6

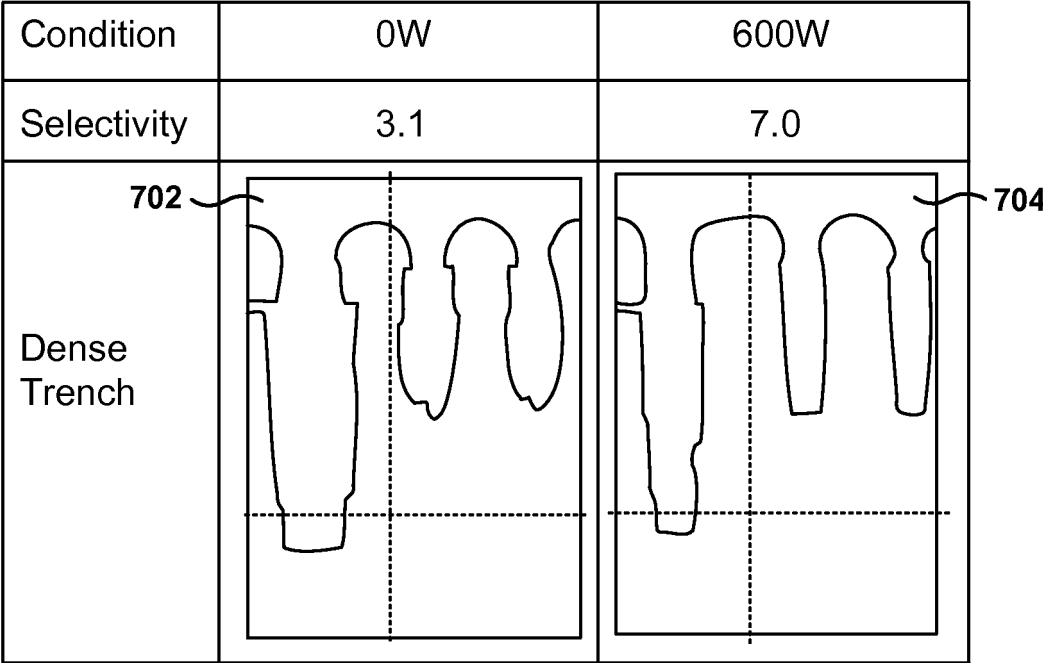
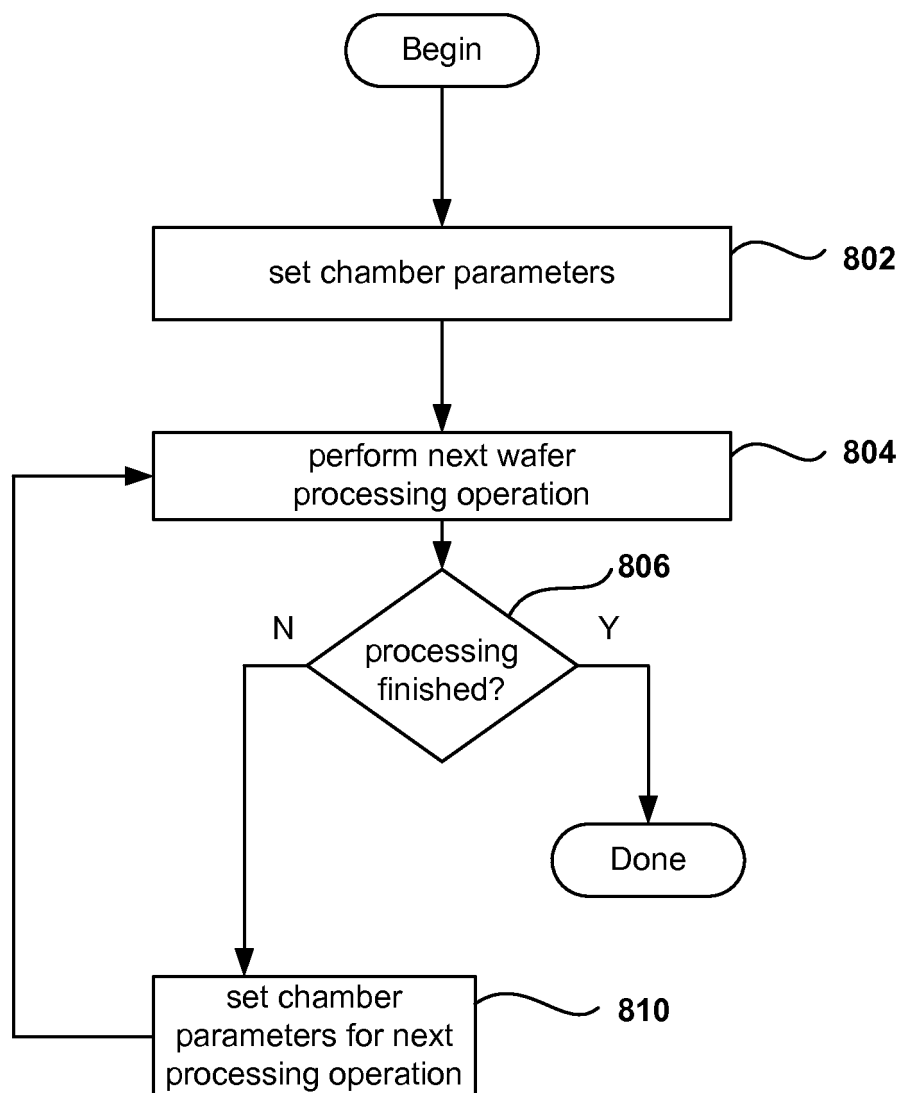


Fig. 7

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**Fig. 8**

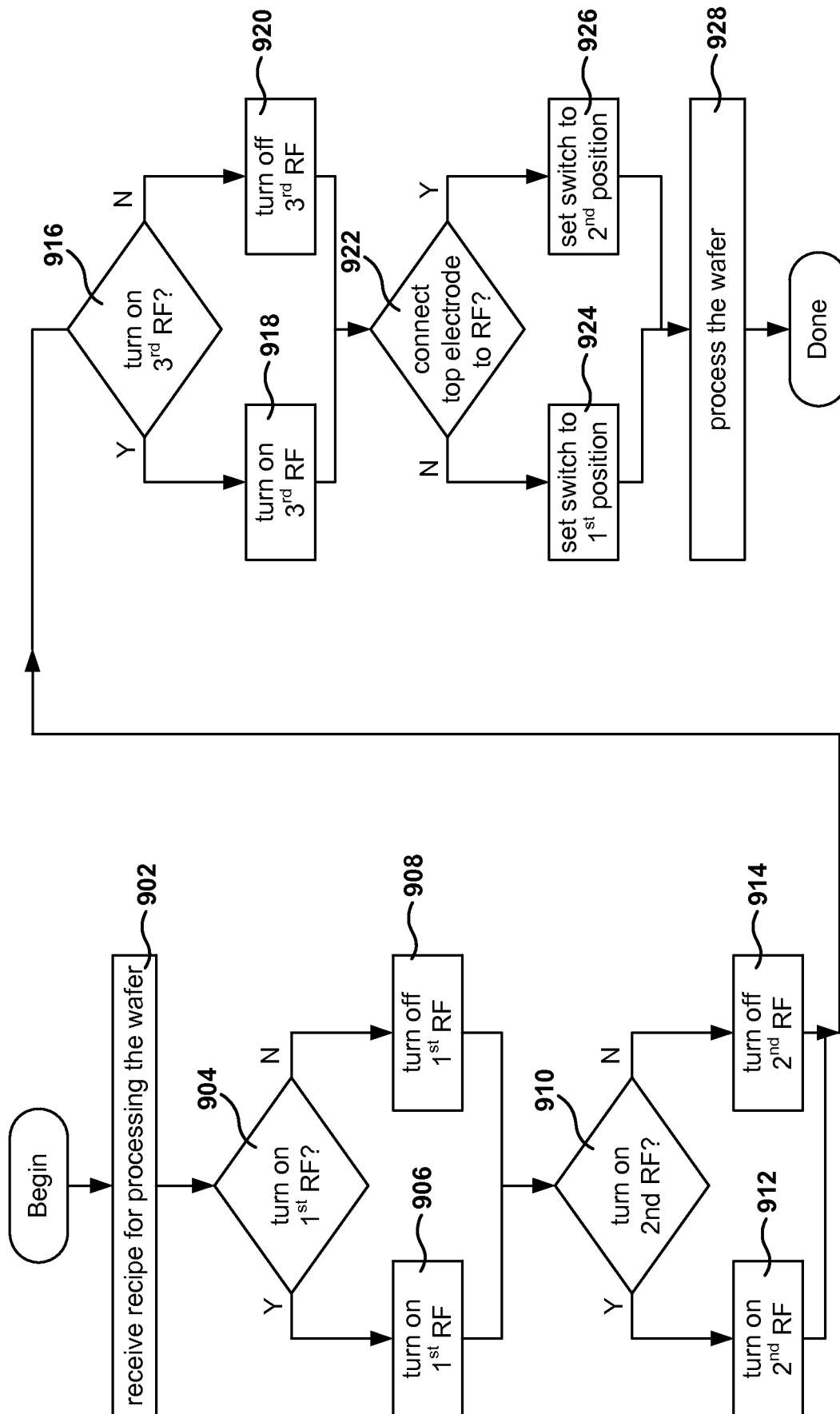
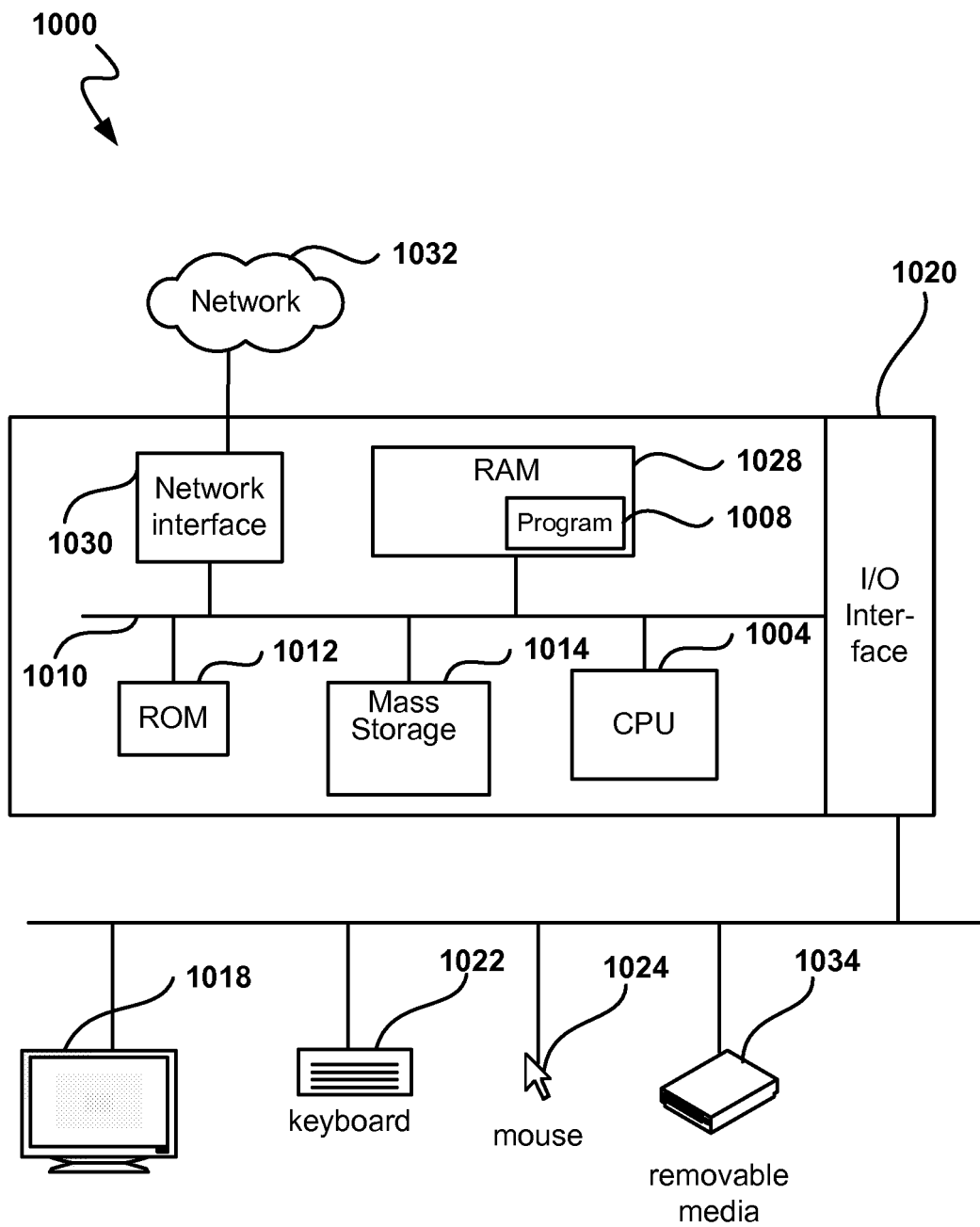


Fig. 9

**Fig. 10**